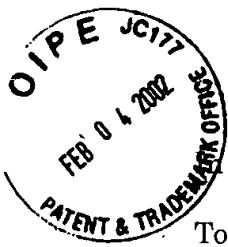


PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



re application of

Toshiaki AOAI, et al.

Attorney Docket No.: Q60206

Appln. No. 09/620,708

Group Art Unit: 1752

Confirmation No.: Not Assigned

Examiner: J. Chu

Filed: July 20, 2000

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TC 1700

For: POSITIVE PHOTORESIST COMPOSITION FOR FAR ULTRAVIOLET EXPOSURE

PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136

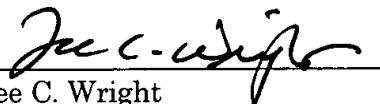
Commissioner for Patents
Washington, D.C. 20231

Sir:

Pursuant to 37 C.F.R. § 1.136, Applicant hereby petitions for an extension of time of one month, extending the time for responding to the Office Action of October 3, 2001 to February 3, 2002.

A check for the statutory fee of \$110.00 is attached. Please charge any additional fees under 37 C.F.R. § 1.16 or § 1.17 necessary to keep this application pending in the Patent and Trademark Office or credit any overpayment to Deposit Account No. 19-4880. A duplicate copy of this sheet is enclosed.

Respectfully submitted,


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